	Application No.	Annling m4(n)	
Notice of Allowability	Application No.	Applicant(s)	
	08/914,868	BJORNARD ET AL.	
	Examiner	Art Unit	
	Audrey Y. Chang	2872	
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in this ap or other appropriate communication GHTS. This application is subject to	plication. If not included n will be mailed in due co	urse. THIS
1. This communication is responsive to <u>June 25, 2002, Augu</u>	<u>ist 4,2003</u> .		
2. X The allowed claim(s) is/are <u>1-6, 7-15, 18-22, 31-34, 36-43,</u>	48-50, 54-62 renumbered as 1-6 ar	<u>nd 8-45</u> .	
3. $\boxtimes$ The drawings filed on <u>19 August 1997</u> are accepted by the	Examiner.		
<ul> <li>4. ☐ Acknowledgment is made of a claim for foreign priority una) ☐ All b) ☐ Some* c) ☐ None of the: <ol> <li>1. ☐ Certified copies of the priority documents have</li> <li>2. ☐ Certified copies of the priority documents have</li> <li>3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received:</li> </ul>	been received. been received in Application No cuments have been received in this	national stage applicatio	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requi	rements
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			TICE OF
6. $\square$ CORRECTED DRAWINGS ( as "replacement sheets") mus			
(a) including changes required by the Notice of Draftspers		-948) attached	
1) hereto or 2) to Paper No./Mail Date		Office action of	
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment of in the C	Thice action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawi he header according to 37 CFR 1.121(	ngs in the front (not the ba	ack) of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT			te the
Attack was and (a)			
Attachment(s)  1. Notice of References Cited (PTO-892)	5. Notice of Informal F	Patent Application (PTO-	152)
2.  Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary		
Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	Paper No./Mail Da 98), 7. ☐ Examiner's Amendo		
4. Examiner's Comment Regarding Requirement for Deposit	8. 🛭 Examiner's Stateme	ent of Reasons for Allow	ance
of Biological Material	9.		

## REASONS FOR ALLOWANCE

## Remark

- This Office Action is in response to applicant's amendment filed on June 25, 2002 and August 4, 2003, which have been entered into the file.
- By these amendments, the applicant has amended claims 1, 8-10, 17, 33, 36-40, 43, 49 and 50, has canceled claims 35, 47 and 51-53, and has newly added claims 54-62.
- Claims 1-5, 7-15, 17-22, 31-34, 36-43, 48-50 and 54-62 remain pending in this application.

## Reasons For Allowance

1. The following is an examiner's statement of reasons for allowance: of the prior art references considered, none has disclosed a coated article or a process for making a coated article as described below and set forth in the claims:

With regard to claim 1, the coated article is comprised of a temperature sensitive substrate having a melting point lower than glass and an anti-reflection coating. The anti-reflection coating including a plurality of layers wherein the plurality of layers including a reactively sputtered high refractive index material layer with index refraction ranged between 1.9 and 2.2 and is selected from the group of materials claimed. The high refractive index material layer that is farthest from the substrate has an optical thickness about one quarter to one third of a wavelength ranged between 480 and 560 nanometers.

With regard to claim 8, the process of making a coated article comprises the steps of providing a temperature sensitive substrate having a melting point lower than glass for receiving an anti-reflection coating. The anti-reflection coating including a plurality of layers wherein the plurality of layers including a sputtered high refractive index material layer with index refraction ranged between 1.9 to 2.2 and is selected from the group of materials claimed. The high refractive index material layer that is

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farthest from the substrate has an optical thickness about one quarter to one third of a wavelength ranged between 480 and 560 nanometers.

With regard to claims 9 and 10, the anti-reflection coating for a substrate is comprised of *four* layers with the specific layer materials and specific physics thickness of the layers as claimed in each of the claims.

With regard to claim 33, the article comprising a temperature sensitive substrate having a melting point lower than glass and an anti-reflection coating. The anti-reflection coating including a plurality of layers wherein the plurality of layers including a high refractive index material layer with index refraction ranged between 1.9 and 2.2 and is selected from the group of materials claimed. The high refractive index material layer that is farthest from the substrate has an optical thickness about one quarter to one third of a wavelength ranged between 480 and 560 nanometers.

With regard to claims 36 and 37, an article comprising a temperature sensitive substrate having a melting point lower than glass and an anti-reflection coating. The anti-reflection coating including a plurality of layers wherein the plurality of layers including a second and a fourth layer of high refractive index material with index refraction ranged between 1.9 to 2.2 and is selected from the group of materials claimed. The second layer (claim 36) and the fourth layer (claim 37) each have a specific physical layer thickness as set forth in the claim.

With regard to claims 38-40, and 43, the method for providing an anti-reflection coating to a plastic substrate and an antireflection coating for a plastic substrate, wherein the anti-reflection coating has a four layer structure with the second layer and fourth layer composed of a tin-doped indium oxide, or is selected form the group of materials claimed in the claims (40 and 43) and the optical thickness for the second layer is about one-quarter to one-third of a wavelength from 480 to 560 nanometers.

With regard to claims 49 and 50, an antireflection coating for a *plastic substrate*, wherein the anti-reflection coating is comprised of a plurality of layers that includes a *high refractive index material* 

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layer having index of refraction ranged between 1.9 and 2.2 and is selected from the *group* of materials *claimed*. The high refractive index material layer that is farthest from the substrate has an optical thickness about one quarter to one third of a wavelength ranged between 480 and 560 nanometers.

The specific high refractive index materials claimed in the instant application have the advantage of not generate a lot of heat during sputtering coating process to the substrate which therefore allows the anti-reflection coating to be formed on a temperature sensitive substrate with melting point lower than glass, such as plastic.

The prior art reference US patent issued to Okaniwa (PN. 5,667,880) teaches an electroconductive antireflection film having high refractive index layer composed of material such as indium tin oxide with an optical thickness ranged between one quarter to one third of a wavelength in visible light but this reference does not teach the substrate is a temperature sensitive substrate such as plastic substrate. Furthermore, Okaniwa teaches that the anti-reflection film includes other high refractive index material that will impart large heat in the depositing process, which therefore cannot be formed on a temperature sensitive substrate such as plastic.

## **Contact Information**

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Audrey Y. Chang whose telephone number is 571-272-2309. The examiner can normally be reached on Monday-Friday (8:00-4:30), alternative Mondays off.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Drew Dunn can be reached on 571-272-2312. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Audrey Y. Chang, Ph.D. Brimary Examiner

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A. Chang, Ph.D.